

Oral Session

Keynote/Invited	Presentation NO	Presentation date	Time to start	Time to finish	Account: First name	Account: Middle name	Account: FAMILY NAME	Account: Affiliation	Abstract title
Chairperson: (Naoto Ohtake, Tokyo Institute of Technology)									
	A-7-O28-001	28 Sep.	10:30	10:45	Haruhiko		ITO	Nagaoka University of Technology	Source of nitrogen atoms of amorphous carbon nitride films fabricated with microwave-plasma CVD processes
	A-7-O28-002	28 Sep.	10:45	11:00	Shigeyuki		SEKI	Sendai National College of Technology	Fabrication of Zirconia Thin Film by Spray CVD Method: Influence of Al Composition and Acetylacetone Concentration of the Spray Solutions
	A-7-O28-003	28 Sep.	11:00	11:15	Putri	Septembriani	LOSO	Undergraduate student	Technology of Organic Fertilizer Pastes As a New Innovation Recovery Engineering for Degraded Soil
	A-7-O28-004	28 Sep.	11:15	11:30	Hiroki		AKASAKA	Tokyo Institute of Technology	Detection of Chemical Attack on Amorphous Carbon Films Using SPR Phenomenon

Poster Session

Presentation NO	Presentation date	Time to start	Time to finish	Account: First name	Account: Middle name	Account: FAMILY NAME	Account: Affiliation	Abstract title
A-7-P25-001	25 Sep.	18:00	20:00	Yoshiyuki		NISHIMURA	Graduate School of Kanto Gakuin University	Anisotropic Growth Electroless Copper Plating for Pattern Formation Without Resist
A-7-P25-002	25 Sep.	18:00	20:00	Satoshi		KAMEMOTO	Toray Industries, Inc.	Low-temperature Curable Positive-tone Photosensitive Polyimide Coatings for Next-generation Semiconductors
A-7-P25-003	25 Sep.	18:00	20:00	Kohtaro		OKADA	Nagaoka University of Technology	Fabrication of a-CNx films by RF-plasma decomposition of BrCN
A-7-P25-004	25 Sep.	18:00	20:00	Yuichi		SAKURADA	Tokyo Institute of Technology	Detection of Bulk Defects of DLC Films Deposited by Pulse Plasma CVD
A-7-P25-005	25 Sep.	18:00	20:00	Rie		GAPPA	Nagaoka University of Tec.	Analysis of Dissociative Excitation Reaction of Tetramethylsilane with Microwave Discharge Flow of Ar
A-7-P25-006	25 Sep.	18:00	20:00	Toshiyuki		MARUYAMA	TOYAMA Co.,Ltd.	MoS2 Coating for Low Friction Sliding Part in Ultrahigh Vacuum
A-7-P25-007	25 Sep.	18:00	20:00	Hidetoshi		MAEDA	Tokyo Institute of Technology	Synthesis of diamond films by plasma enhanced hot-filament CVD at low substrate temperature
A-7-P25-008	25 Sep.	18:00	20:00	Hironori		MARUTA	Tokyo Institute of Technology	Graphitization of surface of DLC films